

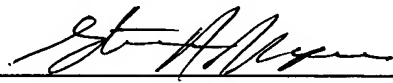


been made or that no other material information as defined in 37 C.F.R. § 1.56(b) exists.

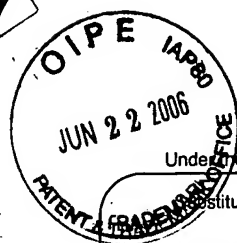
Applicants respectfully request that the Examiner review the foregoing references and request that they be made of record in the file history of the above-captioned application.

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Respectfully submitted,  
HELLER EHRMAN LLP

By:   
Steven A. Moore  
Registration No. 55,462

**Address all correspondence to:**  
Customer No. 33123  
HELLER EHRMAN LLP  
4350 La Jolla Village Drive, 7<sup>th</sup> Floor  
San Diego, CA 92122-1246  
Telephone: (858) 450-8400 Facsimile: (858) 450-8499



Institute for form 1449A/PTO

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

(Use as many sheets as necessary)

Sheet 1 of 8

**Complete if Known**

Application Number	10/765,223
Filing Date	01/26/2004
First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young
Attorney Docket Number	38203-6081B

**U. S. PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
		US- 4,757,207	07/1988	Chappelow et al	
		US- 4,861,148	08/1989	Sato et al	
		US- 4,929,083	05/1990	Brunner	
		US- 5,124,927	06/1992	Hopewell et al	
		US- 5,262,257	11/1993	Fukuda et al	
		US- 5,285,236	02/1994	Jain	
		US- 5,438,413	08/1995	Mazor et al	
		US- 5,444,538	08/1995	Pellegrini	
		US- 5,477,058	12/1995	Sato	
		US- 5,700,602	12/1997	Dao et al	
		US- 5,757,507	05/1998	Ausschnitt et al	
		US- 5,805,290	09/1998	Ausschnitt et al	
		US- 5,824,441	10/1998	Farrow et al	
		US- 5,877,861	03/1999	Ausschnitt et al	
		US- 5,953,128	09/1999	Ausschnitt et al	
		US- 6,023,338	02/2000	Bareket	
		US- 6,064,486	05/2000	Chen et al	
		US- 6,079,256	06/2000	Bareket	

**FOREIGN PATENT DOCUMENTS**

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		Country Code <sup>3</sup> "Number" <sup>4</sup> "Kind Code" <sup>5</sup> (if known)				

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		us- 6,130,750	10/2000	Ausschnitt et al	
		us- 6,137,578	10/2000	Ausschnitt	
		us- 6,142,641	11/2000	Cohen et al	
		us- 6,143,621	11/2000	Tzeng et al	
		us- 6,153,886	11/2000	Hagiwara et al	
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		us- 6,737,207	05/2004	Imai	
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Sheet **3** of **8**

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Application Number	10/765,223
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First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young
Attorney Docket Number	38203-6081B

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First Named Inventor	Smith et al
Art Unit	1756
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Attorney Docket Number	38203-6081B

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		Armitage et al, Analysis of overlay distortion patterns, SPIE Vol. 921, 207:221, 1988	
		Biesterbos et al., A New Lens for Submicron Lithography and its Consequences for Wafer Stepper Design, SPIE Vol. 633, Optical Microlithography V, 34:43, 1986	
		Bjorkholm et al., Reduction Imaging at 14nm Using Multilayer-Coated Optics: Printing of Features Smaller than 0.1 Micron, Journal Vacuum Science and Technology, B 8(6), 1509:1513, Nov/Dec 1990	
		Bruning, Optical Lithography – Thirty Years and Three Orders of Magnitude, SPIE Vol. 3051, 14:27, 1997	
		Brunner, Impact of Lens Aberrations on Optical Lithography, IMB Journal of Research and Development: Optical Lithography, 41(1-2): 57-67 (1997)	
		Cote et al., Micrascan™ III Performance of a Third Generation, Catadioptric Step and Scan Lithographic Tool, SPIE Vol. 3051, 806:816, 1997	
		DeJule, Mix-and-Match: A Necessary Choice, Semiconductor International, 66:76, Feb 2000	
		Dooly et al, Stepper Matching for Optimum Line Performance, SPIE Vol. 3051, 426:432, 1997	
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		Goodwin et al., Expanding Capabilities in Existing Fabs with Lithography Tool-Matching, Solid State Technology, 97:106, June 2000	

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Application Number 10/765,223

Filing Date 01/26/2004

First Named Inventor Smith et al

Art Unit 1756

Examiner Name C. Young

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of

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Attorney Docket Number 38203-6081B

**NON PATENT LITERATURE DOCUMENTS**

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		Handbook of Microlithography, Micromachining and Microfabrication, Book: Vol. 1, "Microlithography", Rai-Choudhury, P. (Ed.), SPIE Optical Engineering Press, SPIE, Bellingham, Washington, pp. 417-418 (1997)	
		Hasan et al., Automated Electrical Measurements of Registration Errors in Step and Repeat Optical Lithography Systems, IEEE Transactions on Electron Devices, Vol. ED-27, No. 12, 2304:2312, December 1980	
		Kemp et al., "A 'Golden Standard' Wafer Design for Optical Stepper Characterization", Proc. of SPIE, Vol. 1464, pp. 260-266, 1991	
		KLA 5105, "Linewidth and Misregistration System", KLA 5105 Product Specification, KLA Instruments Corporation, 2 pages (1995)	
		KLA 5200, "Value-added Overlay Metrology for Advanced Lithography", KLA 5200 Product Specification, KLA Instruments Corporation, 2 pages (1996)	
		Kodama et al., Measuring System XY-5I, K. SPIE Vol. 2439, 144:155, 1995	
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		Lin, "The Attenuated Phase-Shifting Mask", Solid State Technology, Special Series/Advanced Lithography, 35(1): 43-47 (1992)	
		MacMillan et al, "Analysis of Image Field Placement Deviations of a 5X Microlithographic Reduction Lens", SPIE, 334:78-89 (1982)	
		Martin et al, Measuring Fab Overlay Programs, SPIE Conference on Metrology, Inspection, and Process Control for Microlithography XIII, 64:71, March 1999	

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		McFadden, C. et al, A Computer Aided Engineering Workstation for Registration Control, SPIE Vol. 1087, 255:266, 1989	
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		Proglor et al., Method to Budget and Optimize Total Device Overlay, SPIE Vol. 3679, 193:207, 1999	

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		Starikov et al., Accuracy of Overlay Measurements: Tool and Mark Asymmetry Effects, Optical Engineering, 1298:1309, 1992	
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		Takac et al, "Self-Calibration in Two-Dimensions: The Experiment", SPIE, 2725:130-146 1996	
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		van den Brink et al., Matching Performance for Multiple Wafer Steppers using an Advanced Metrology Procedure, SPIE Vol. 921, 180:197, 1988	

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		van den Brink et al., Step and Scan and Step and Repeat, a Technology Comparison, SPIE Vol. 2726, 734:753	
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		Yost et al., Lens Matching and Distortion Testing in a Multi-Stepper, Sub-Micron Environment, SPIE Vol. 1087, 233:244, 1989	
		Zavec, Life Beyond Mix-and-Match: Controlling Sub-0.18 Micron Overlay Errors, Semiconductor International, July 2000	
		Zavec, "Machine Models and Registration", SPIE Critical Reviews of Optical Science and Technology, CR52:134-159 (1994)	
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